Compositional Abruptness at the InAs-on-GaSb Interface:

Optimizing Growth by Using the Sb Desorption Signature

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Definition of Problem

- Excessive anion intermixing at the InAs-on-(In,Ga)Sb interface is usually observed.
- Anion intermixing is not well-controlled, and its origins are not well-understood.
- Inability to control anion intermixing results in poor reproducibility of type-II transition energies and recombination efficiency, as well as inconsistent match with theory.

In this work, we ...

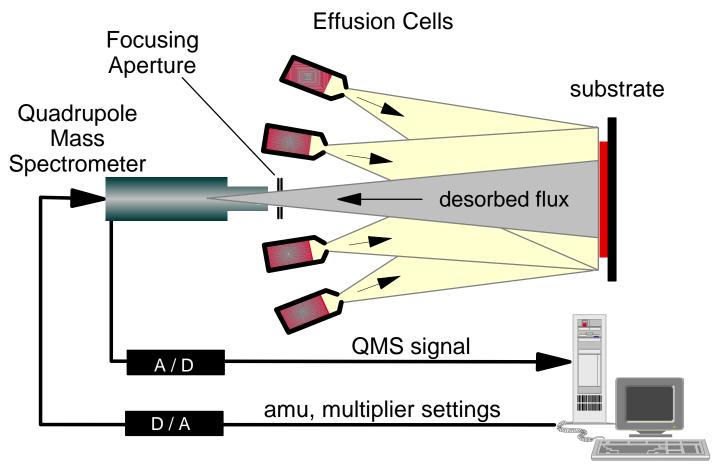
- ... use in-situ desorption mass spectrometry (DMS) to study the origins and kinetics of anion intermixing,
- ... directly observe 1) As-for-Sb exchange in GaSb, and
 2) Sb-surface riding and incorporation in InAs,

... and conclude that ...

- ... there is always a large population of excess Sb at the GaSb surface that can mix into the InAs layer,
- ... to achieve a compositionally abrupt interface, one must remove the excess Sb without damaging the GaSb layer. A precisely controlled As-soak step may be the key.
- Sb desorption signature allows the optimization of MBE parameters to improve compositional abruptness.

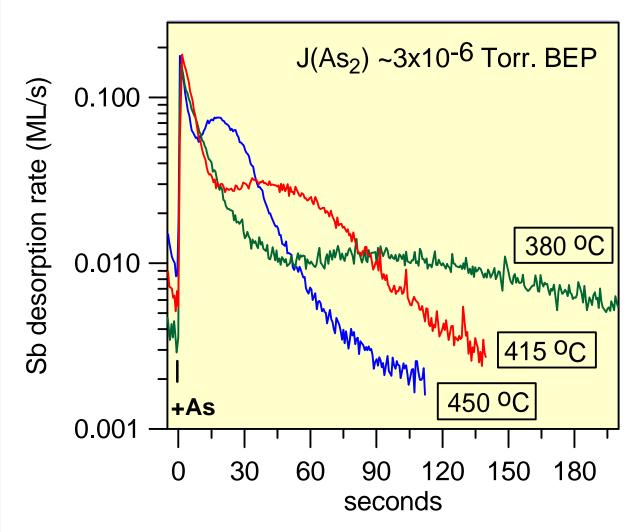
Desorption Mass Spectrometry in MBE



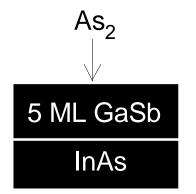




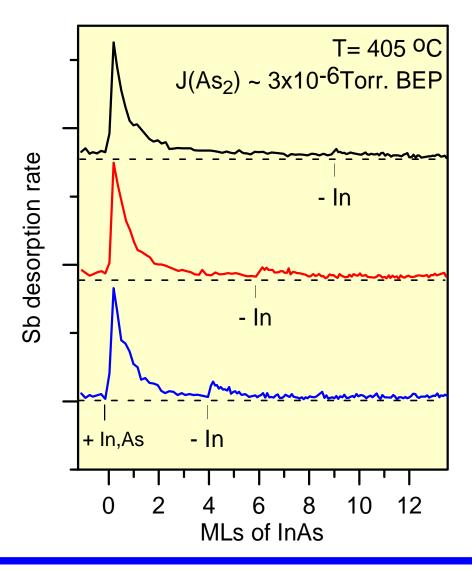
GaSb is unstable when exposed to As₂



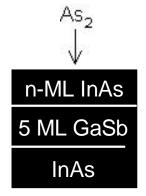
As-for-Sb exchange at the surface is followed by bulk exchange and almost all of the Sb in the 5 ML's is eventually purged by exposure to arsenic at normal growth temperatures.



Excess Sb rides the surface and incorporates into InAs

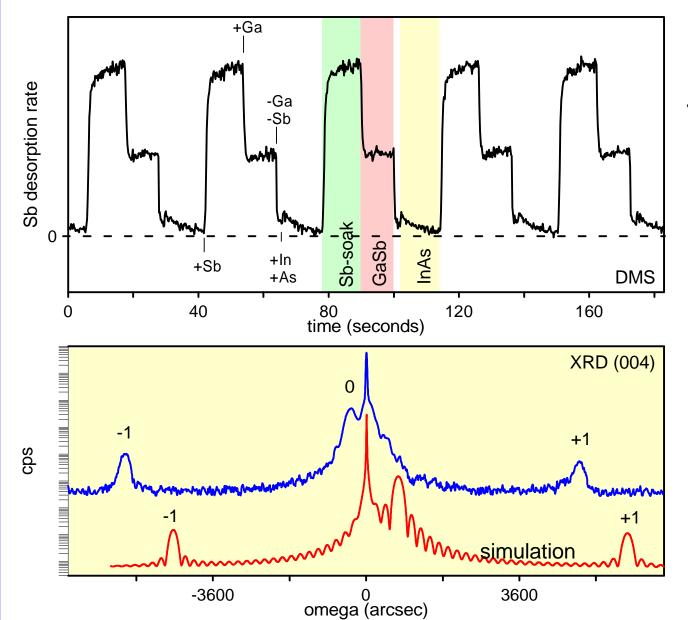


Sb desorption during InAs growth indicates Sb surface riding. Enhanced desorption after growth-interrupt indicates kinetic limitation to surface-riding, and incorporation of Sb into the InAs layer. Sb surface population diminshes as the growth surface moves further away from the InAs-on-GaSb interface.





InAs(6ML)/GaSb(6ML) SLS- no soak at InAs-on-GaSb interface

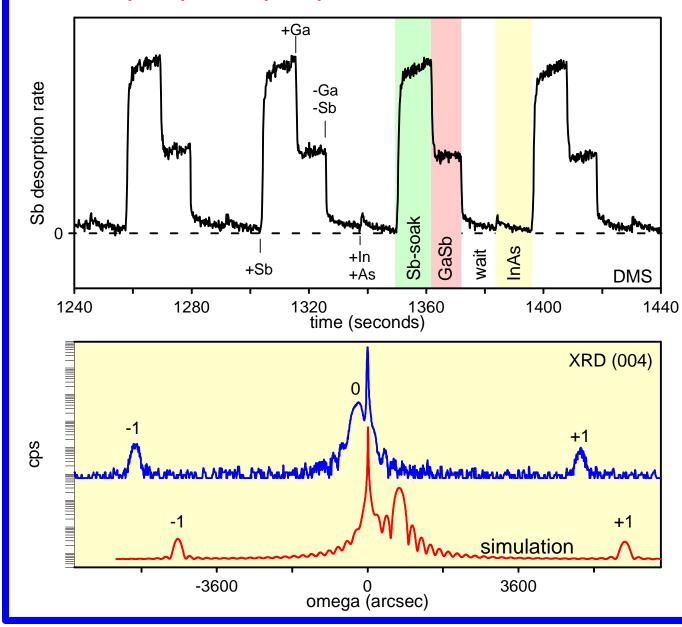


T=400 $^{\circ}$ C J(As₂)=2x10⁻⁶ Torr. J(Sb₂)=1.5x10⁻⁶ Torr. R(GaSb)=0.58 ML/s R(InAs)=0.5 ML/s

Excess Sb at the GaSb surface incorporates into InAs and results in 0.15% average compressive strain in the SLS.



InAs(6ML)/GaSb(6ML) SLS- 12s wait at the InAs-on-GaSb interface

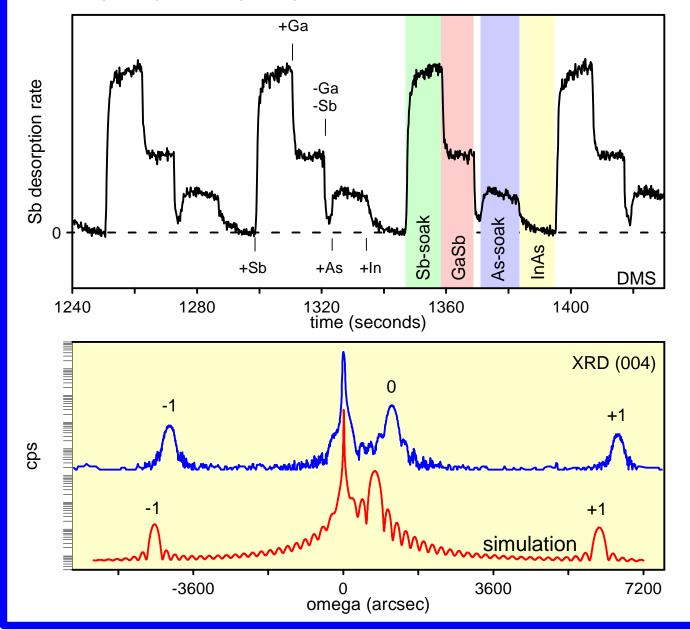


Sb in InAs still results in ~0.12 % compressive strain in SLS.

Waiting for the excess Sb population to leave the GaSb surface on its own has minimal effect. (i.e. need something to accelerate Sb removal).



InAs(6ML)/GaSb(6ML) SLS- 12s As-soak at the InAs-on-GaSb interface

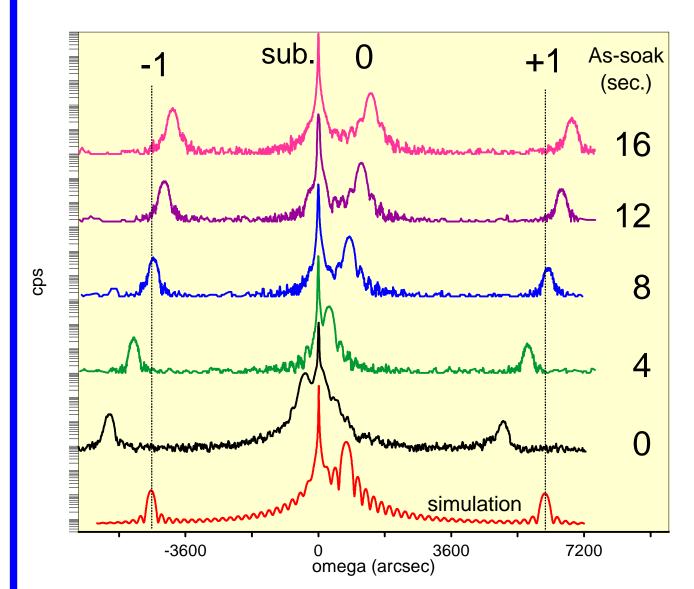


As can efficiently remove Sb but an excessive Assoak can remove more than the necessary amount of Sb.

12 sec. As-soak at these growth conditions has resulted in 0.45 % tensile strain in the SLS, 0.16% more than the ideal SLS.



InAs(6)/GaSb(6) SLS- As-soak time varied



Given a set of MBE growth parameters, the As-soak time can be optimized to give the required SLS strain. Based on desorption measurements, this condition corresponds to improved compositional abruptness at the InAs-on-GaSb interface.

